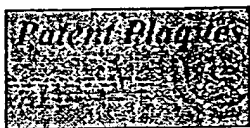


[Home](#) | [Search](#) | [Order](#) | [Shopping Cart](#) | [Login](#) | [Site Map](#) | [Help](#)



JP11268438A2: IMAGE FORMING MATERIAL

[View Images \(1 pages\)](#) | [View INPADOC only](#)

Country: JP Japan

Kind: A2 Document Laid Open to Public Inspection

Inventor(s): KAWAMURA KOICHI


Applicant(s): FUJI PHOTO FILM CO LTD
[News, Profiles, Stocks and More about this company](#)

Issued/Filed Dates: Oct. 5, 1999 / March 23, 1998

Application Number: JP1998000074630

IPC Class: B41N 1/14; G03F 7/004; G03F 7/032;

Abstract: **Problem to be solved:** To provide an image forming material being suitable for a lithographic printing plate, which is excellent in image forming properties (a sensitivity, a development latitude).
Solution: This image forming material contains a polymer binder which is water-insoluble and soluble with an alkali aqueous solution, and an infrared ray absorber having a thermally decomposable sulfonate group. At unexposed parts, the infrared absorber having the thermally decomposable sulfonate group reduces the melting speed of an alkali-soluble polymer binder, and at exposed parts, a sulfonic acid of a coloring matter which is generated by a decomposition of the infrared ray absorber, increases the melting speed of the alkali-soluble polymer binder. By this method, a difference between both parts becomes larger, and a favorable image formation becomes possible.
COPYRIGHT: (C)1999, JPO

Family:  [Show 23 known family members](#)

Other Abstract Info: CHEMABS 131(15)206999Q DERABS C1999-470981

Foreign References: (No patents reference this one)



Alternative
Searches



[Patent Number](#)



[Boolean Text](#)



[Advanced Text](#)

What is claimed is:

1. A photosensitive negative image recording material for a planographic printing plate having an image recording layer containing the following components on a support:

- a compound (A) which is degraded by the action of light or heat to generate an acid,
- a cross-linking agent (B) which cross-links in the presence of an acid,
- at least one alkali-soluble resin (C),
- an infrared absorbing agent (D), and
- at least one amino acid or derivative thereof wherein the amino acid is selected from the group consisting of glycine, β -alanine, valine, norvaline, leucine, norleucine, phenylalanine, tyrosine, diiodotyrosine, surinamine, serine, proline, hydroxyproline, tryptophan, thyroxine, cystine, cysteine, γ -aminobutyric acid, glutamine, lysine, hydroxylysine, arginine and histidine.

Background/Summary: [Show background/summary](#)

Drawing Descriptions: [Show drawing descriptions](#)

Description of Preferred Embodiments: [Show description of preferred embodiments](#)

Foreign References:

Publication	Country	Date	IPC Class
EP1997000784233	European Patent Office (EPO)	7 /1997	

Other Abstract Info: CHEMABS 129(01)010678Y CHEMABS 129(01)010679Z DERABS C1998-337596 DERABS C1998-337597

Other References:

- A. Lamola. et al, Chemically Amplified Resists in Solid State Technology, Aug. 1991, pp. 53-60. (8 pages) [20 patents reference this \[Article info\]](#)

Article info links by



[Nominate this invention for the Gallery...](#)

Alternative Searches


 [Patent Number](#)

 [Boolean Text](#)

 [Advanced Text](#)

Browse

 [U.S. Class by title](#)

 [U.S. Class by number](#)

 [IBM Technical Disclosure Bulletin](#)

[Privacy](#) | [Legal](#) | [Gallery](#) | [IP Pages](#) | [Advertising](#) | [FAQ](#) | [Contact Us](#)